

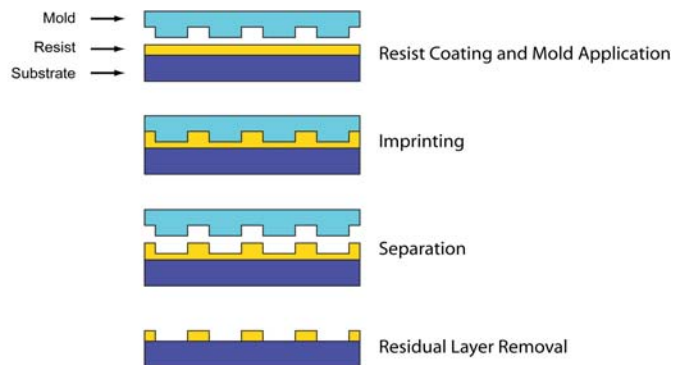
# NXR-1000 Series Thermal Nanoimprint Resists

# Nanoimprint Solutions



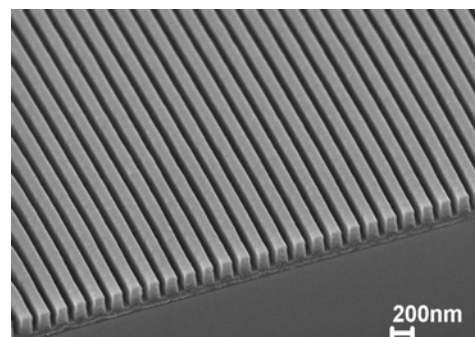
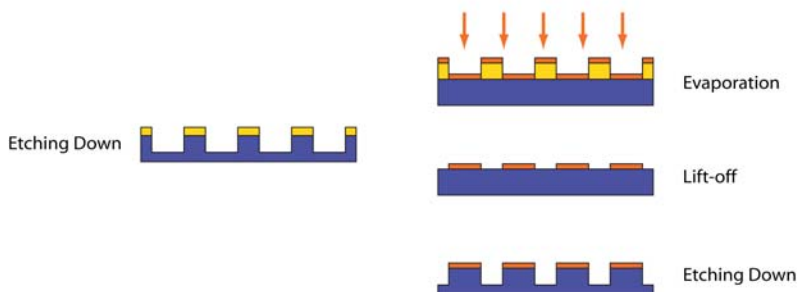
Machines   Masks   Resists   Processes

*NXR-1000 series resists are general purpose thermal nanoimprint resists designed for both sub-10 nm patterning in future nanostructure engineering and today's microfabrication. They offer excellent adhesion, excellent flow characteristics at imprint temperature, excellent thermal stability at room temperature, high etch resistance in plasma, and good lift-off properties, all of which make them ideal for nanoimprint applications.*

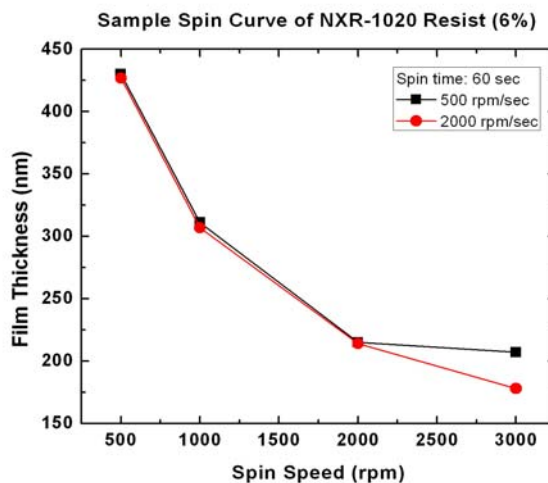


## Key Features

- Sub-10 nm resolution
- Low imprint temperature and pressure
- Stable properties at room temperature
- Strong adhesion to substrate
- Excellent flow property
- Suitable for direct etch and lift-off processes



NXR-1000 Series	NXR-1010	NXR-1020
Imprint pressure	> 80 psi	> 80 psi
Imprint temperature	120 °C	120 °C
Thickness range	250 – 1000 nm	50 – 400 nm
Pattern Transfer	Anisotropic O2 RIE	Anisotropic O2 RIE
Spin coating	Yes (spin curve available)	Yes (spin curve available)
Lift-off (solvent)	Yes (Tetrahydrofuran)	Yes (Acetone)
Resist removal	Tetrahydrofuran or RCA #1	Acetone or RCA #1



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<http://www.nanonex.com>

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The specifications may be updated without notice.